

Design of advanced MoS₂/Si heterojunction photovoltaics.

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Among single junction photovoltaics, heterojunction solar cells based on crystalline silicon and amorphous silicon present the best efficiencies [1]. However, amorphous silicon can present high recombination rates, low conductivity and cause parasitic absorption [2].

We propose a model of photovoltaics cell in which the amorphous silicon is replaced by a thin layer of molybdenum disulfide MoS₂ [3]. MoS₂ is a two-dimensional material with a lamellar structure belonging to the class of transition metal dichalcogenides (TMD). Having the advantage of being naturally abundant and non-toxic, its lamellar structure also gives it interesting properties such as a tunable bandgap according to the thickness. Here we present the first steps towards the development of MoS₂/Si heterojunction photovoltaics that combine performance, non-toxicity and low costs, for applications in autonomous systems for the Internet-Of-Things

We perform numerical simulations with ATLAS Silvaco [4], in order to show the potential of such a structure, and to determine the optimal material parameters and the optimal design. We show that high quantum efficiencies and power conversion efficiencies of about 20 % can be attained.

In order to optimize the deposition of MoS₂, we perform optical and structural characterizations on thin layers of MoS₂ of different thicknesses, deposited on crystalline silicon (001), with silicon dioxide SiO₂ at the interface. The samples have the structure MoS₂/SiO₂ (80nm) /Si. Raman spectroscopy confirms the presence of multilayered MoS₂, while Atomic Force Microscopy (AFM) shows the presence of holes and outgrowths at the surface of the samples. X-ray Photoelectron Spectroscopy shows the presence of oxides in the layers of MoS₂, which explain the outgrowths and crackings seen in AFM. X-Ray Diffraction also confirms that, showing a change in the lattice parameters of MoS₂.

DFT simulations have just been started to figure out the effects of the presence of oxides on the MoS₂ parameters such as electron affinity, electron mobility, which may affect the performance of the photovoltaic devices.

[1] “Best Research-Cell Efficiency Chart.” <https://www.nrel.gov/pv/cell-efficiency.html> (accessed Sep. 13, 2021).

[2] C. Ballif, S. De Wolf, A. Descoedres, and Z. C. Holman, “Chapter Two - Amorphous Silicon/Crystalline Silicon Heterojunction Solar Cells,” in *Semiconductors and Semimetals*, vol. 90, G. P. Willeke and E. R. Weber, Eds. Elsevier, 2014, pp. 73–120. doi: 10.1016/B978-0-12-388417-6.00003-9.

[3] H. Xu et al. / *Materials Letters* 238 (2019) 13–16.

[4] “Silvaco,” *Silvaco*. <https://silvaco.com/dynamicweb/silen/> (accessed Sep. 13, 2021).

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